



Cheiron School 2012

**X-ray Free Electron Laser
Part-2: Beamline Part**

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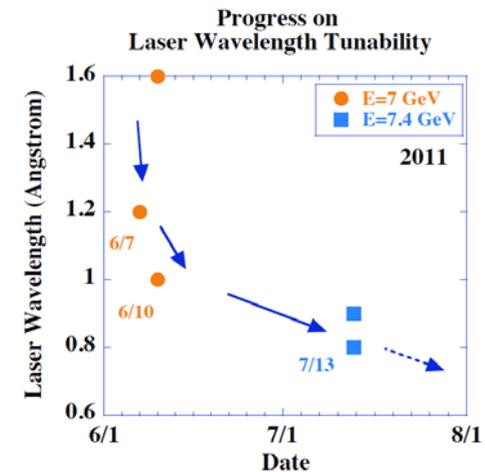
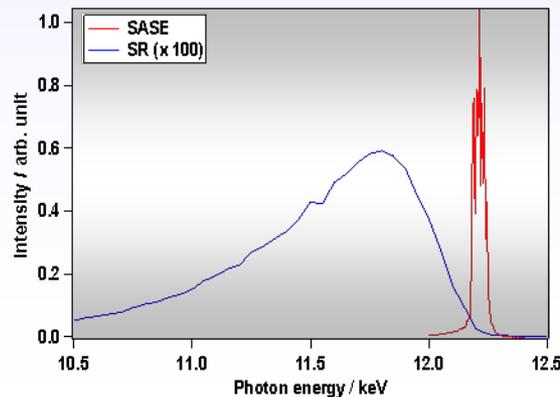
Sep 28, 2012 @SPring-8

First Lasing of SACLA: June 7, 2011

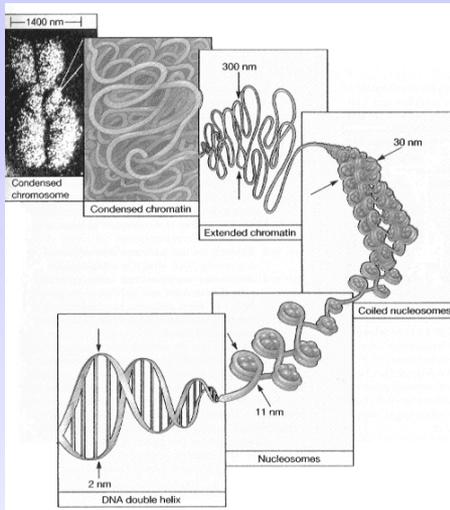


祝 SACLA 発振

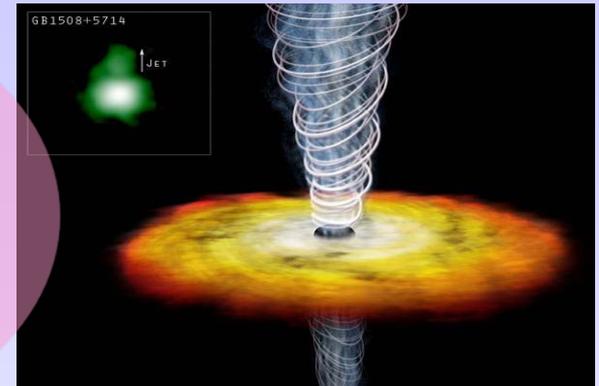
平成18年から国家基幹技術として整備を進めてきたX線自由電子レーザー施設SACLAにて、
平成23年6月7日16時10分 にレーザー発振を確認いたしました。
皆様の今までの応援に感謝し、今後ご期待に沿えるよう一同頑張っております。



XFEL explores new worlds of science



**Brilliance
($\times 10^9$)**



Fundamental Science:
Create Extreme State

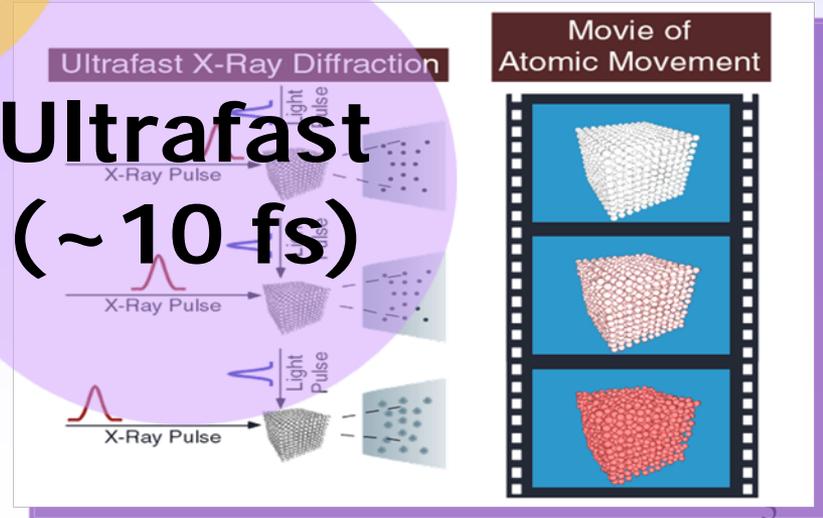
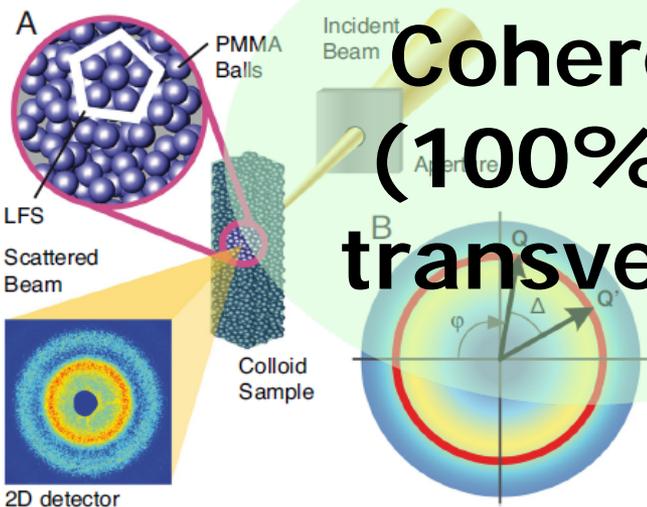
Biology & Medicine: Investigate
non-crystalline materials

XFEL

Environmental & Energy Science:
Probe ultrafast reactions

**Coherent
(100% in
transverse)**

**Ultrafast
(~ 10 fs)**



“Coherence”

Coherent Diffraction Imaging

Transverse coherence

Longitudinal coherence

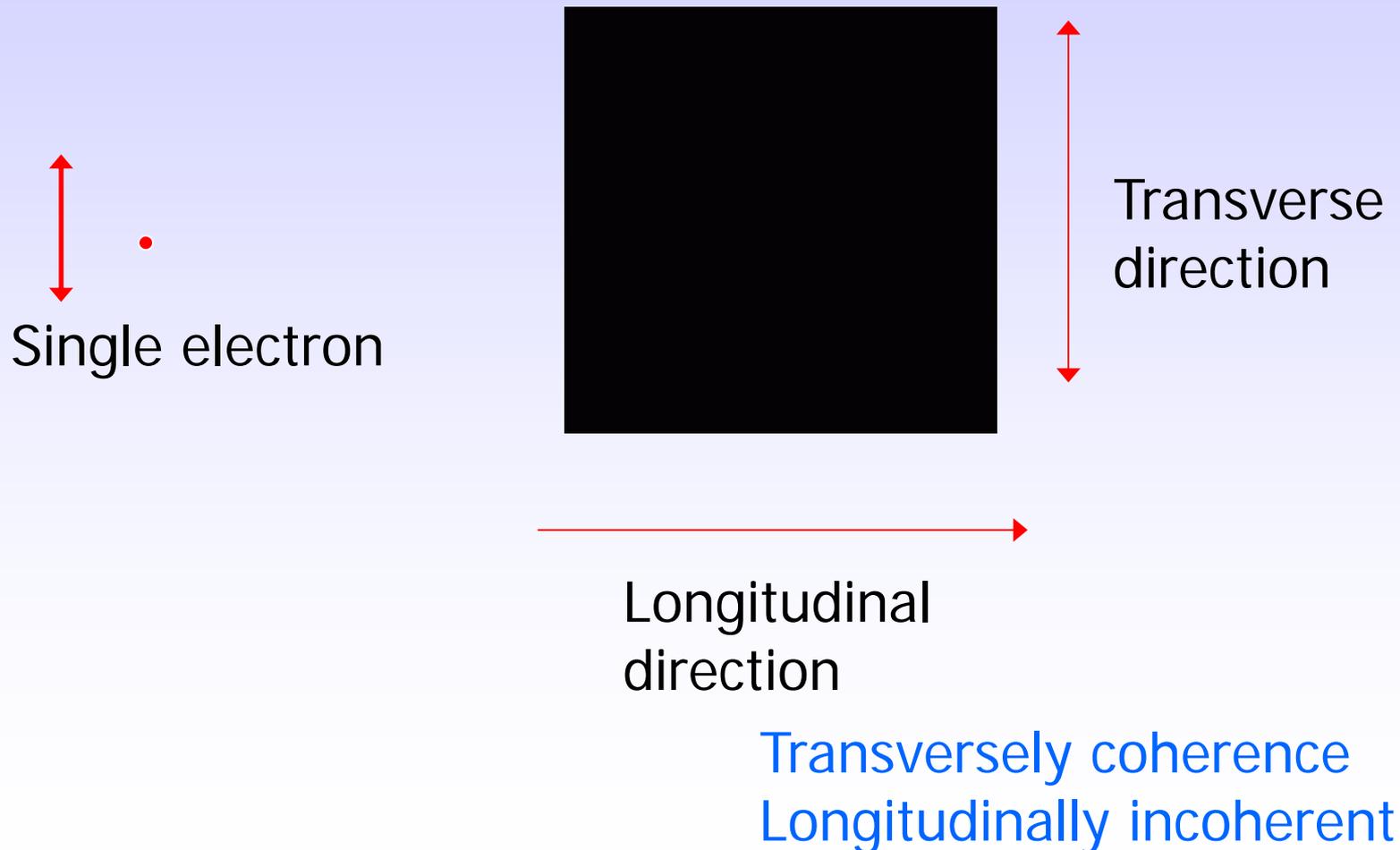
Coherent radiation

Coherent light source

Incoherent scattering ...

Q. Do you have physical images of coherence ?

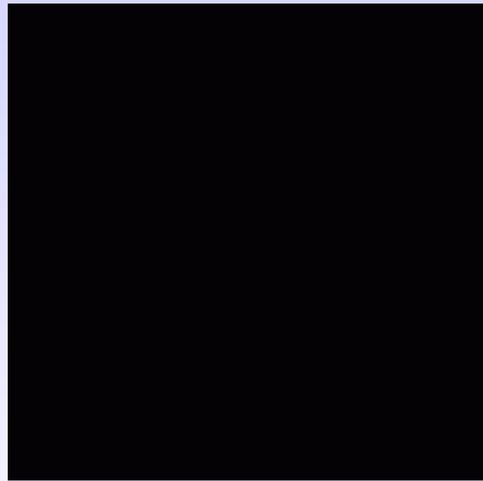
Radiation from single electron



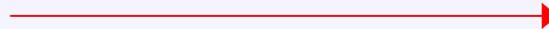
Radiation from “point” source with many electrons



Point source,
Many electrons
in random phase
(Chaotic source)



Transverse
direction



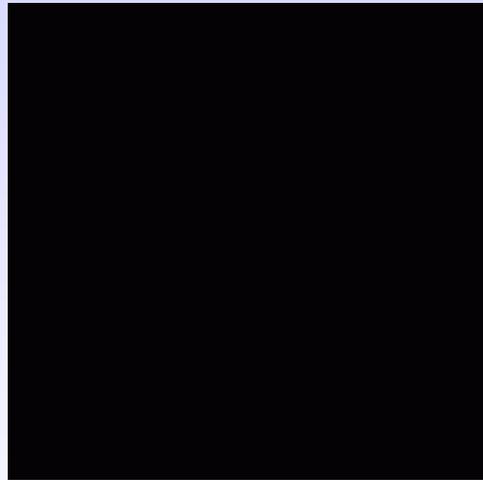
Longitudinal
direction

Transversely coherence
Longitudinally incoherent

Radiation from “extended” source with many electrons



Extended source,
Many electrons
in random phase
(Chaotic source)



Transverse
direction

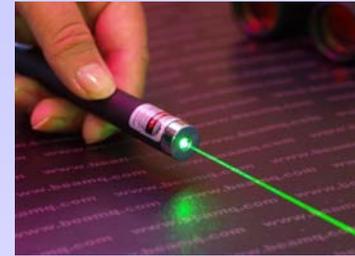
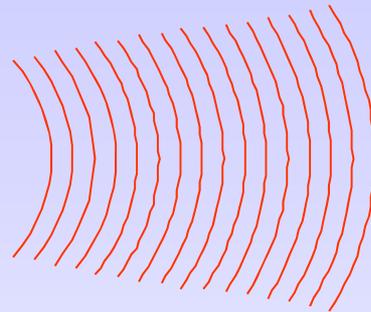


Longitudinal
direction

Transversely incoherence
Longitudinally incoherent

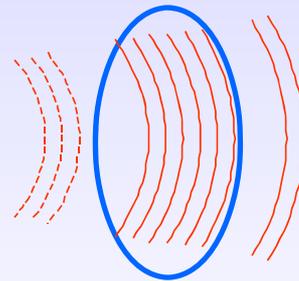
Summary

Coherent source



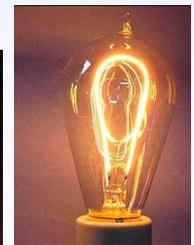
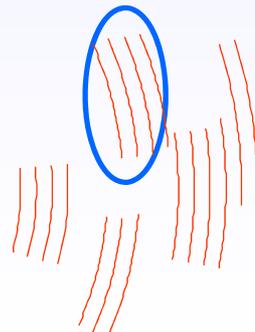
"seeded"-FEL
all electrons in phase

Point source
Multiple electrons



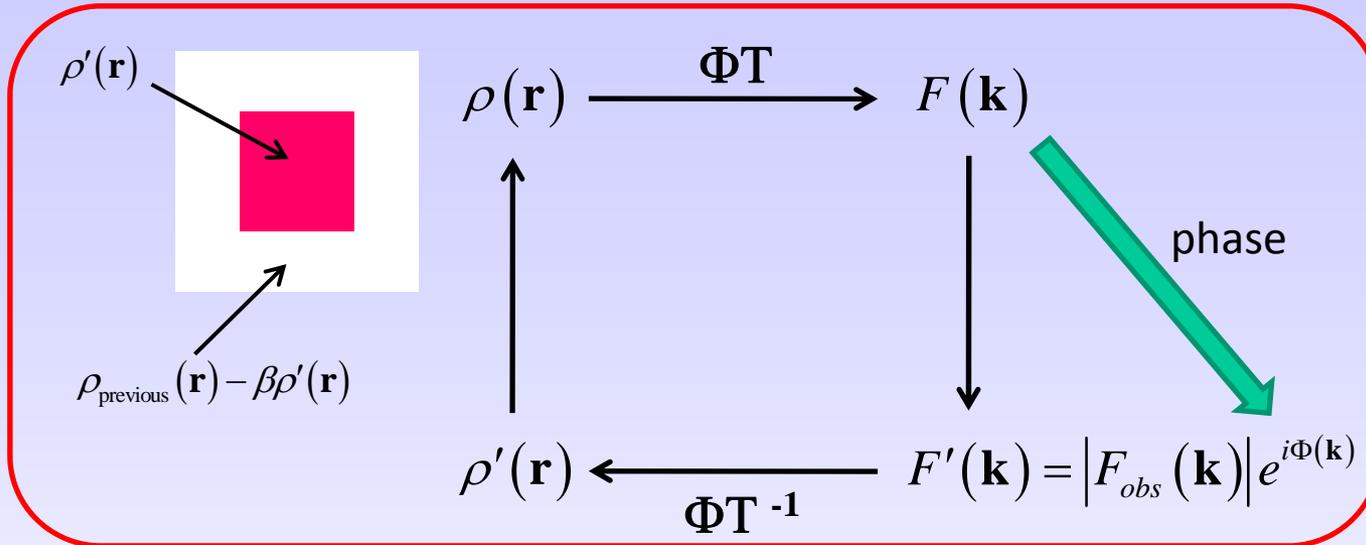
"SASE"-FEL
only neighboring
electrons in phase

Extended source
Multiple electrons



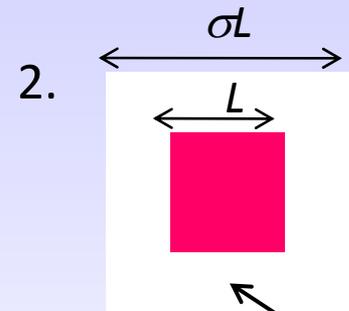
Phase retrieval with HIO (Hybrid-Input-Output) method at oversampling condition

Courtesy of Joti-san

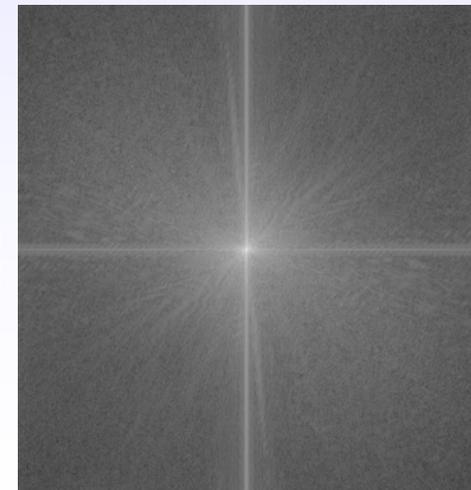
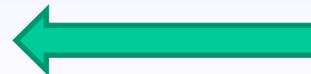
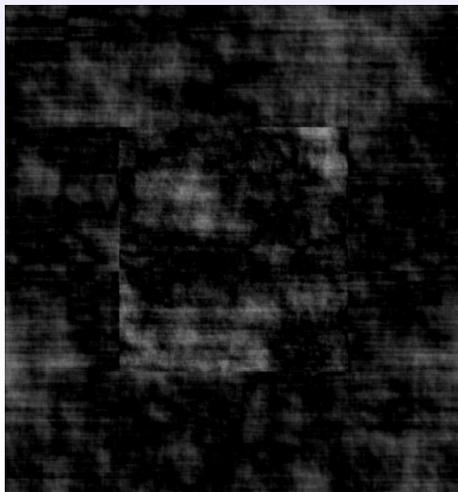


Input

1. $|F_{obs}(\mathbf{k})|$

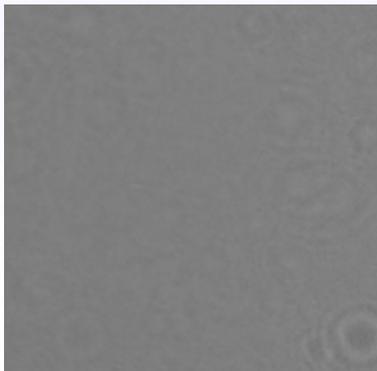
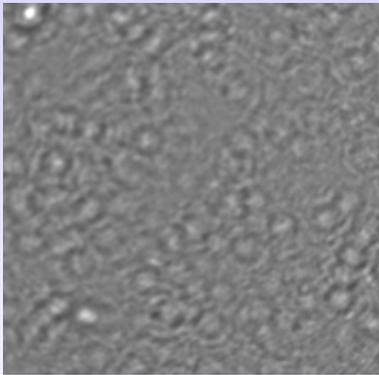


Hybrid Input Output (HIO) Algorithm J.R. Fienup, (1982) *Appl. Opt.* **21**, 2758-2769



Coherent light: dangerous probe for imperfect optics

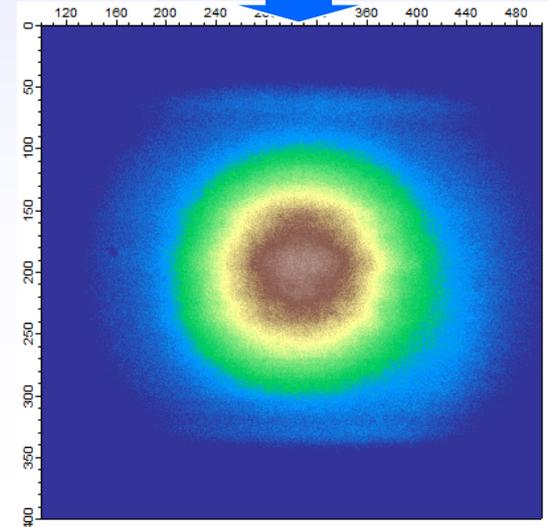
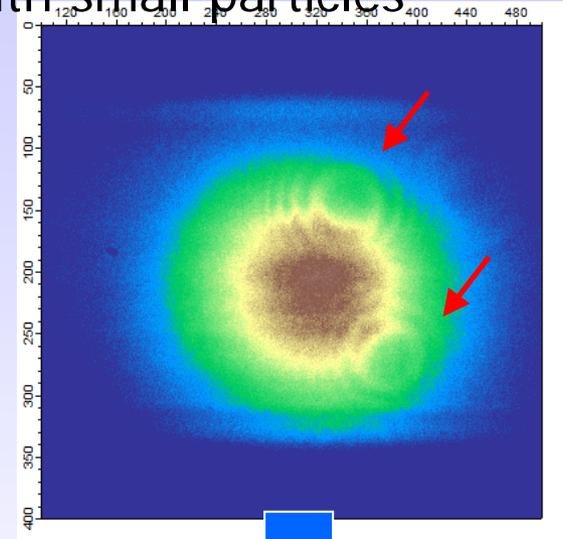
Transmission image from mid-quality beryllium foil with voids



Reflection image from mid-quality mirror

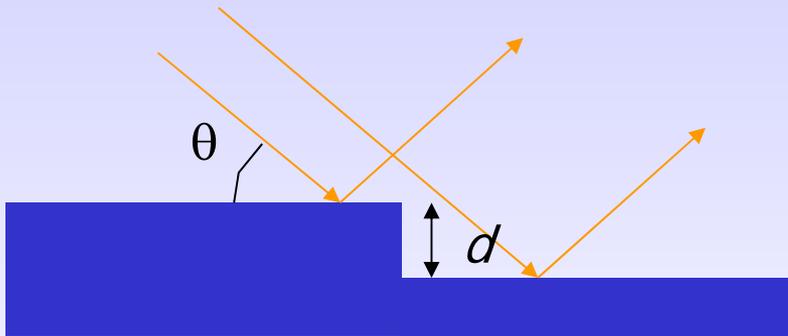


Reflection image of SACLA XFEL from double mirrors with small particles



Mirror requirement

Ultraprecise surface figure is required to prevent unwanted speckles under coherence illumination



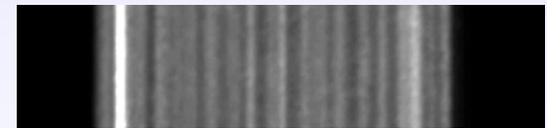
Path difference: $\delta = 2d \sin \theta$

$\delta < \lambda/20$, $\lambda = 0.1 \text{ nm}$, $\theta = 2.5 \text{ mrad}$

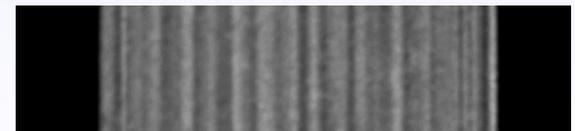
$$d < \frac{\lambda}{40 \sin \theta} = \frac{0.1 \text{ nm}}{40 \times 2.5 \times 10^{-3}} = 1 \text{ nm}$$

1st experiment of Osaka-SP8 collaboration (Mori et al, SPIE 2001)
Plane mirror is illuminated with coherent x-rays @ 1-km BL of SP8

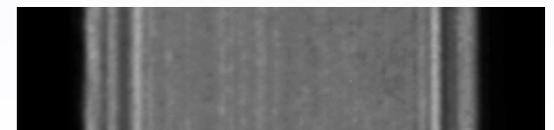
Pre-machined



EEM



EEM+CVM



High peak intensity

“Pulse energy”: J/pls

“Peak power”: W

“Photon flux”: photons/pls

Ex)

Photon flux: 10^{11} photons @ $h\nu=10$ keV, $\tau=10$ fs

Pulse energy: $I = 1.6 \times 10^{-19}$ (J/eV) $\times 10^{11} \times 10000$ (eV)
 $= 1.6 \times 10^{-4}$ (J) = 160 μ J

Peak power: $P = 160 \mu\text{J} / 10 \text{ fs} = 16 \text{ GW}$

XFEL pulse can melt or ablate materials

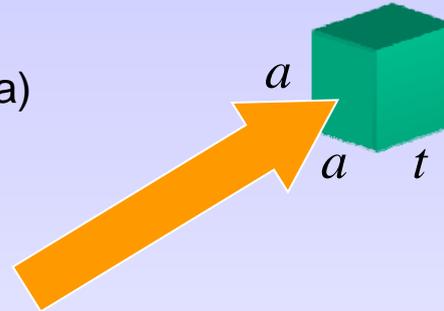
Absorbed energy > melting (ablation) threshold

P-beam Intensity: I (# of photon per unit area)

Absorbed photon per cell: $\mu I a^2 t$

Number of atoms in cell: $\rho N_A a^2 t / M$

Absorbed photon number per atom



$$\frac{\mu I M}{\rho N_A}$$

μ : linear absorption coeff.

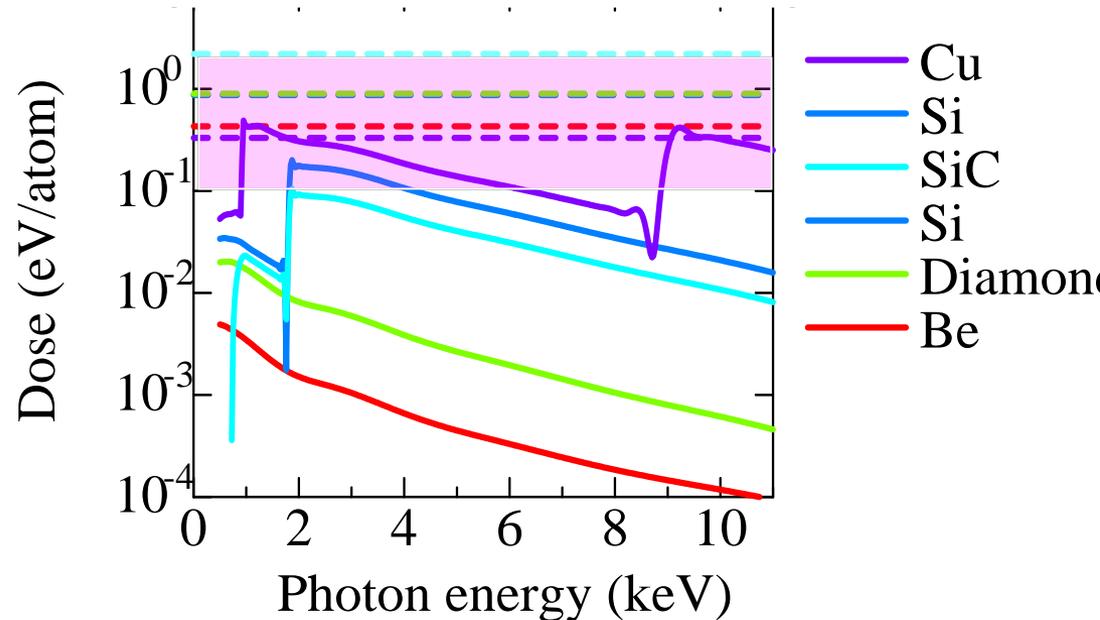
ρ : density

M : average atomic weight

N_A : Avogadro number

➡ Dose (eV/atom)

Calculation for unfocused XFEL beam @SACLA



How to use XFEL ?

High peak power/flux in very short pulses
Can easily destroy samples after irradiation
Shot-to-shot change of pulse characters

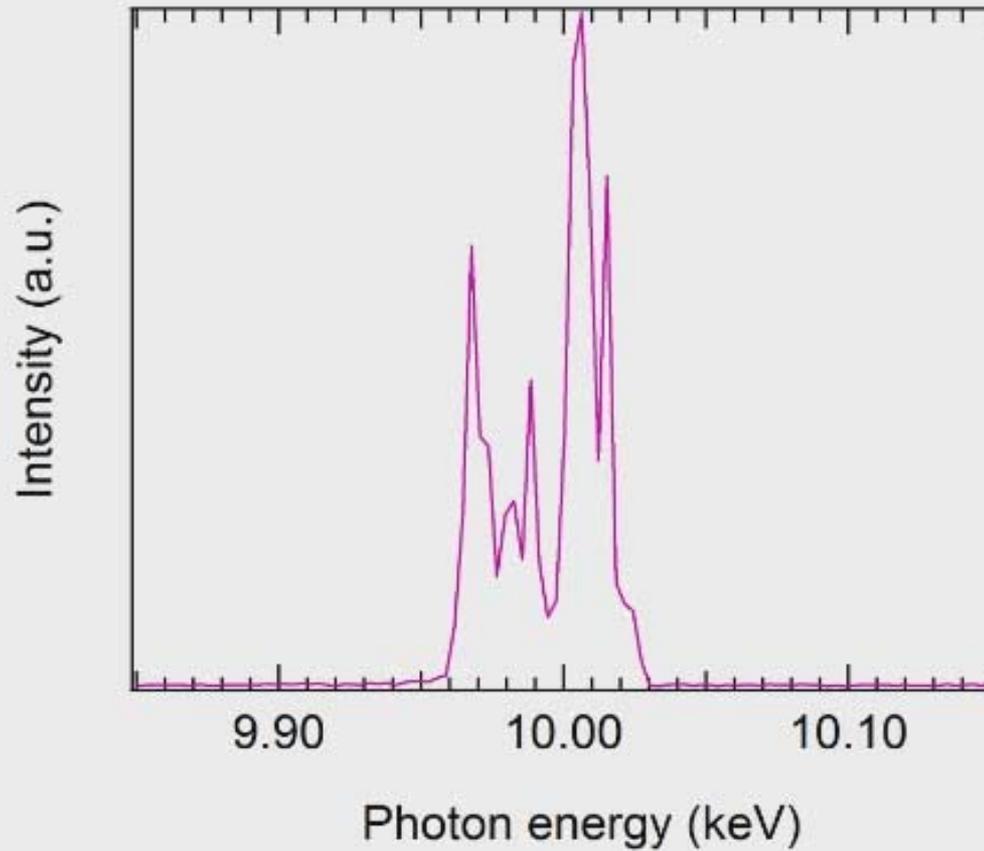


Single-shot measurement

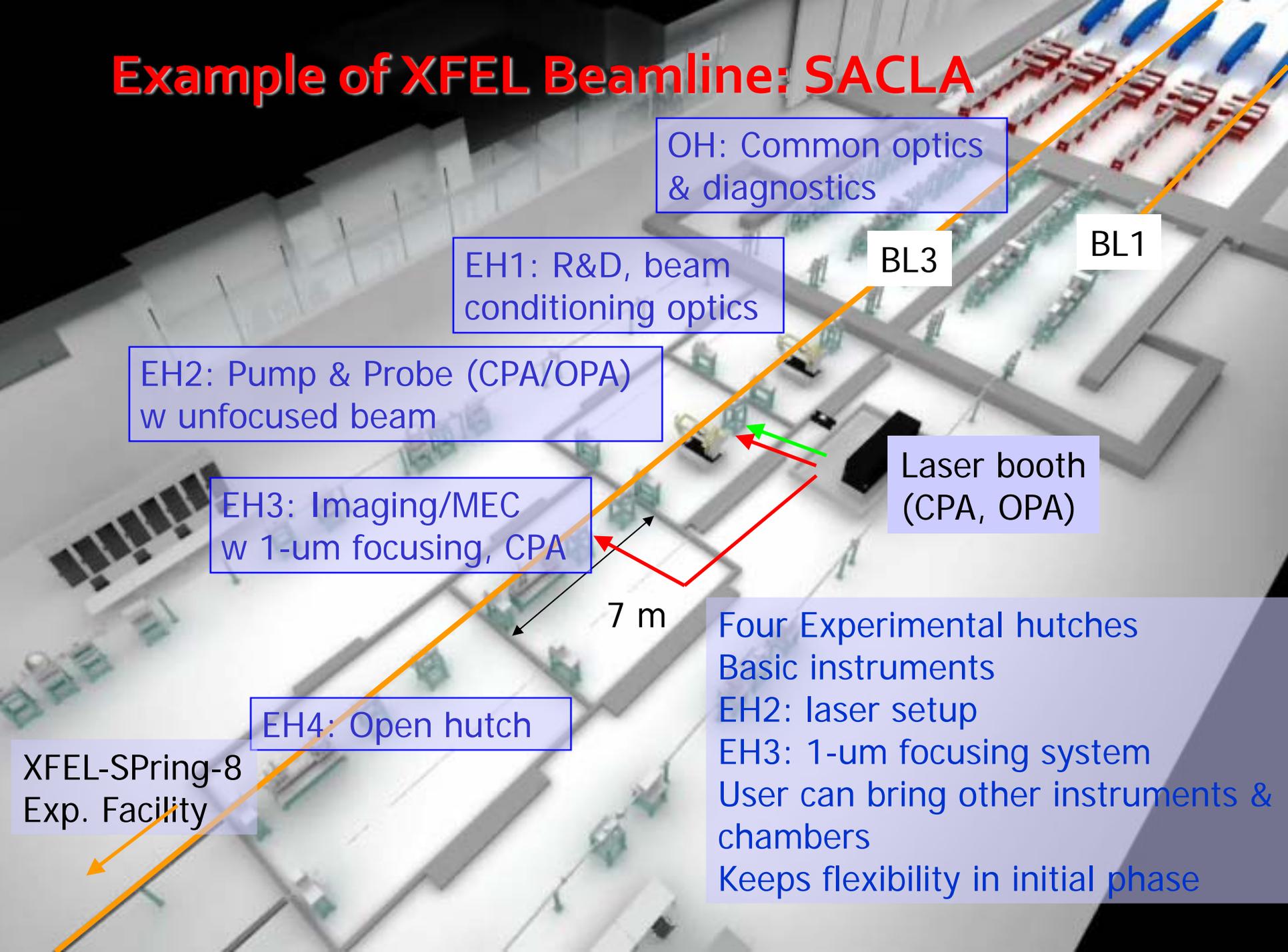
SACLA Single-shot spectra

Central energy is stable

Spike profiles change in every shot



Example of XFEL Beamline: SACLA



OH: Common optics & diagnostics

EH1: R&D, beam conditioning optics

EH2: Pump & Probe (CPA/OPA) w unfocused beam

EH3: Imaging/MEC w 1-um focusing, CPA

EH4: Open hutch

BL3

BL1

Laser booth (CPA, OPA)

7 m

Four Experimental hutches
Basic instruments
EH2: laser setup
EH3: 1-um focusing system
User can bring other instruments & chambers
Keeps flexibility in initial phase

XFEL-SPring-8
Exp. Facility